

AMENDMENTS TO THE CLAIMS

1. (Currently Amended) A fabrication method for a color filter panel of a display device, the method comprising:

forming a color filter layer on a substrate, the color filter layer defining an opening;

forming a photosensitive layer on the color filter layer; and

forming a spacer spaced apart from the color filter layer by back-exposing the photosensitive layer through the opening and removing an unexposed portion of the photosensitive layer, the spacer aligned with the opening in a direction of the back-exposing.

the opening located in a region of the color filter panel corresponding to a corner region of a unit pixel region of a corresponding TFT array panel.

2. (Original) The method of claim 1, wherein in the step of forming the color filter layer, the color filter layer includes first, second and third sub color filter layers.

3. (Original) The method of claim 2, further comprising:

forming a black matrix between the first, second and third sub color filter layers as the first, second and third sub color filter layers are formed.

4. (Original) The method of claim 3, wherein the opening is automatically formed as the black matrix and the first, second and third sub color filter layers are formed.

5. (Previously Presented) The method of claim 3, wherein in the step of forming the black matrix, the black matrix is a stack of first, second and third organic layers being used to form the first, second and third sub color filter layers, and wherein the step of forming the color filter layer includes forming the each of the first, second and third sub color filter layers lower than the stack of first, second and third organic layers.

6. (Original) The method of claim 2, wherein the step of forming the color filter layer includes:

forming a first organic layer on the substrate;
exposing the first organic layer using a first mask; and
developing the exposed first organic layer to form the first sub color filter layer and to define the opening.

7. (Original) The method of claim 6, wherein the step of forming the color filter layer further includes:

forming a second organic layer entirely over a resultant structure; exposing the second organic layer using a second mask; and
developing the exposed second organic layer to form the second sub color filter layer and to define the opening.

8. (Original) The method of claim 7, wherein the step of forming the color filter layer further includes:

forming a third organic layer entirely over a resultant structure; exposing the third organic layer using a third mask; and

developing the exposed third organic layer to form the third sub color filter layer and to define the opening.

9. (Original) The method of claim 8, wherein each of the first, second and third masks includes a pattern corresponding to the opening, such that this pattern is used to form the opening.

10. (Original) The method of claim 1, wherein in the step of forming the color filter layer, the color filter layer includes an ultraviolet ray absorbent material.

11. (Original) The method of claim 1, wherein the step of forming the spacer is performed using a glass filter.

12. (Original) The method of claim 11, wherein the glass filter blocks a wavelength of at least 360 nm.

13. (Original) The method of claim 1, further comprising:
forming a common electrode on the color filter layer; and
forming an alignment layer on the common electrode and the spacer.

14. (Original) The method of claim 1, further comprising:

forming an overcoat layer on the color filter layer; and

forming an alignment layer on the spacer.

15. (Original) The method of claim 1, wherein the spacer is formed by using a negative type photosensitive resin.

16-33. (Cancelled)

34. (Previously Presented) The method of claim 1, wherein the step of forming the spacer includes forming the spacer entirely outside of the opening.

35. (Previously Presented) The method of claim 1, wherein the step of forming the spacer includes forming the spacer spaced apart from the substrate.

36. (Previously Presented) The method of claim 1, wherein the step of forming the color filter layer includes forming a plurality of sub color filter layers such that the opening is between one of the sub color filter layers and a black matrix, and the opening is separated by the black matrix from another one of the sub color filter layers immediately adjacent to the one of the sub color filter layers.

37. (New) A fabrication method for a color filter panel of a display device, the method comprising:

forming a color filter layer on a substrate, the color filter layer having an opening, by sequentially forming first, second and third sub color filter layers;

forming the opening in the color filter layer and a black matrix on the substrate as the first, second and third sub color filter layers are formed by sequentially masking and etching a respective one of the first, second and third sub color filter layers;

forming an overcoat layer on the black matrix and the color filter layer;

forming a common electrode layer on the overcoat layer;

forming a photosensitive layer on the common electrode layer; and

forming a spacer in the photosensitive layer by back-exposing the photosensitive layer through the opening and removing an unexposed portion of the photosensitive layer.

38. (New) The method of claim 37, wherein the opening is located in a region of the color filter panel corresponding to a corner region of a unit pixel region of a corresponding TFT array panel.